

**PASSIVE GAS FLOW MANAGEMENT AND FILTRATION DEVICE
FOR USE IN AN EXCIMER OR TRANSVERSE DISCHARGE LASER**

ABSTRACT OF THE DISCLOSURE

5 [0046] The present invention provides systems and methods for filtering particles and
 assisting gas flow management within laser systems. In one embodiment, a laser apparatus
 (100) includes an elongate laser chamber defining a chamber cavity (130) and an electrode
 structure (140) disposed therein. The electrode structure includes an anode (148) spaced
 apart from a cathode (146). The laser includes an elongate baffle (174) disposed in the laser
10 chamber. The baffle is adapted to arrest a plurality of particles generated within the chamber.
 In this manner, the baffle operates as a passive filtration system to help filter particles
 generated within the chamber during laser operation, and may further provide gas flow
 management capabilities.

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